

## **Training and usage policy**

- Training is restricted
- Thickness allowed upto 20nm
- Silicon , Germanium substrates are allowed
- Cleaning of sample should be done before submitting for deposition.
- Fresh wafers should be RCA cleaned

## **ALD Precursor changing policy**

1. Precursor will be changed every Tuesday between 10am to 11am
2. Authorized users must send mail by Monday 8pm for precursor change.
3. Decision of changing the precursors will be taken depending on slot booking requests and mails from AUs.

For eg:

- 1) Precursors loaded in tool : Al, Hf, Ti

If we get request sequentially for Zn, Zr, Si and DEA then depending on date stamp request will be attended.

New precursor Zn, Zr and Si will be installed in that week.

DEA will be installed next Tuesday.

- 2) If we receive request for combination of two or three precursors then those will be also attended as per request date

If we get request for Zn, Al & Hf ,Zr

New precursor Zn, Al and Hf will be installed.

4. Email will be sent to censtudent and censtaff informing precursors available for that week.